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②國玄東華大學

課 網 Course Outline

材料科學與工程學系一般組

中文課程名稱 Course Name in Chinese		穿透式電子顯微鏡					
英文課程名稱 Course Name in English		Transmission Electron Microscopy					
科目代碼 Course Code		MS_52700	班 別 Degree	碩士班 Master's			
修別 Type		選修 Elective	學分數 Credit(s)	3. 0	時 數 Hour(s)	3. 0	
先修課程 Prerequisite		大學部的物理冶金(一)(二)或晶體結構與繞射原理或研究所的高等物理冶					
課程目標 Course Objectives							
介紹掃描式電子顯微鏡、穿透式電子顯微鏡的原理,並應用於材料組織、成份、 與結構分析研究工作上。							
系教育目標 Dept.'s Education Objectives							
1	建立專業知識基礎 Set the professional knowledge foundation						
2	培養專業實驗技能 Train the professional experimental skill						
3	養成獨立研究能力 Insure capabilit	ty of independent research					
4	養成優質社會人格 Form the positive social character						
5	開展國際視野 Develop global vision						
	系專業能力 Basic Learning Outcomes				力相關性 Correlati between C Objective Dept.'s	課程目標與系專業能 力相關性 Correlation between Course Objectives and Dept.'s Education Objectives	
A	具備材料科學所需的進階物理、化學及數學的知識。 Acquire required advanced physical, chemical, and mathematic knowledge for materials science and engineering.			(0		
В	具備材料科學的進階專業知識,並能應用於解決工程上之問題。 Acquire required advanced professional knowledge for materials science and engineering, applicable in solving engineering problems						

	C 具備獨立研究之能力。 Equipped with capabilities of independent research.	•
Ι	具備專業道德及責任感,與良好的溝通及團隊合作的能力。 Acquire professional morality and responsibility, and capability of quality communication and team cooperation.	•
I	E 具備適當的英文能力,應用於學習與交流。 Acquire English capability used for learning and interaction	n.
	Acquire Engrish capability used for realiting and interaction	111.

圖示說明Illustration : ● 高度相關 Highly correlated ○中度相關 Moderately correlated

課程大綱 Course Outline

- 1. 電子東/材料作用原理 (basic concepts, elastic & inelastic scattering)
- 2. 電子繞射理論與繞射圖分析 (recoprocal space, Bragg reflection & diffuse scattering, indexing spot pattern & Kikuchi pattern, convergent beam diffraction)
- 3. 電子成像原理與組織缺陷分析 (diffraction contrast, phase contrast,

crystal defect characterization)

- 4. 成份分析方法 (x-ray spectroscopy, electron energy-loss spectroscopy)
- 5. 掃描式電子顯微鏡 (SEI, BEI, EDS, EBSD)

資源需求評估(師資專長之聘任、儀器設備的配合・・・等)

Resources Required (e.g. qualifications and expertise, instrument and equipment, etc.)

以具有所開課程專長之教師擔任授課;資料整理所需之電腦、影印機;討論所需 之投影機、幻燈機等教學設備。

課程要求和教學方式之建議

Course Requirements and Suggested Teaching Methods

以指定教材按預訂進度進行教學。教學以講授及討論為主,必要時以相關文獻資 料加以補充

其他

Miscellaneous